Thermal Atomic Layer Etching of Molybdenum Based on Sequential Oxidation and Chlorination Reactions

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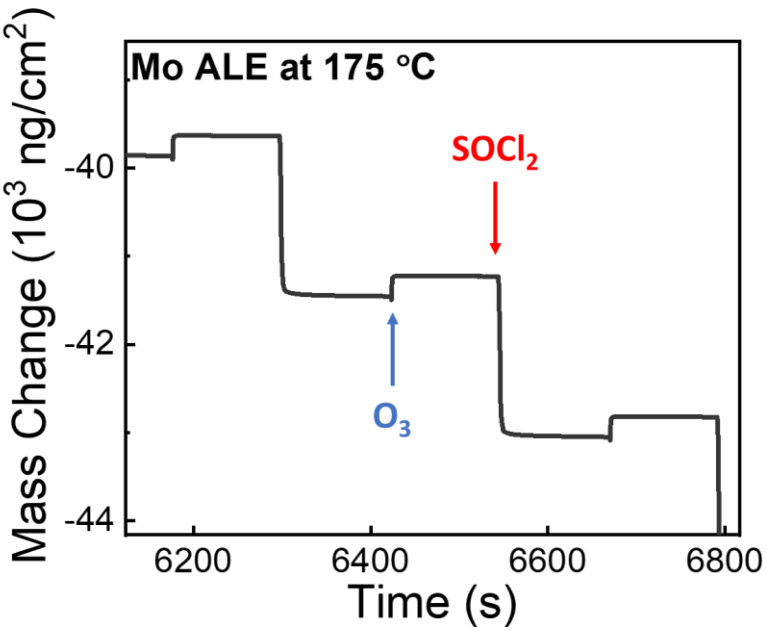

Figure 1. QCM mass change of Mo ALE using O_3 and $SOCl_2$ at 175 °C

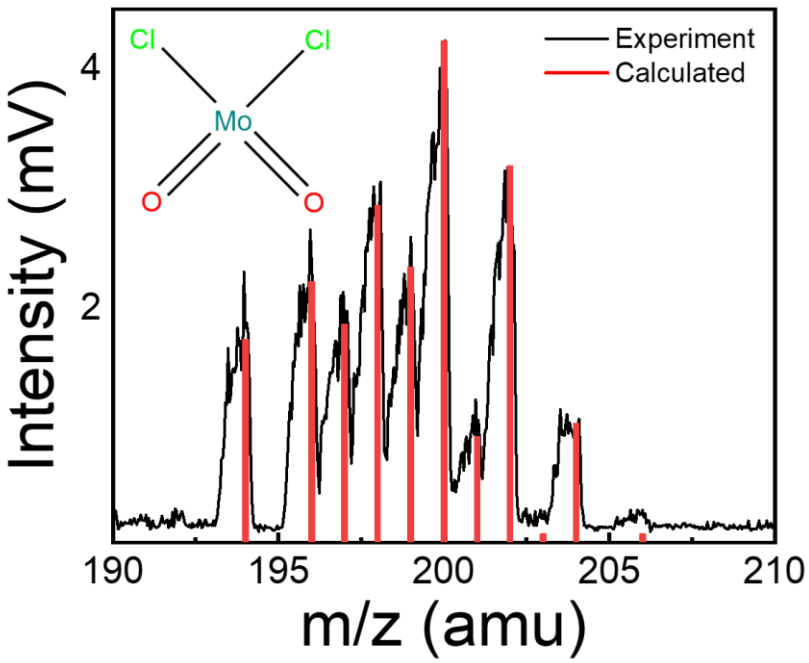

Figure 2. Mass spectrometry results and calculated isotopic spectrum for the molybdenum etch product, MoO_2Cl_2, from the reaction of $SOCl_2$ with MoO_3 powder at 275 °C.